Passive CMOS Strip Detectors Response with Alpha Particles

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Motivation

- * Passive CMOS strip detectors were fabricated stitching 2 different reticles
 * They show excellent performance in
- different setups and irradiations [1-5]
- Here we want to show that they give excellent results with alpha particles

Sensors

* Fabricated at LFoundry [6],
150 nm CMOS process
* 150 µm thick FZ wafer with
3-5 kΩ resistivity
* Strips 4.1 cm and 2.1 cm

Setup

- Measurements taken with Am241
 source on top of the detector, located at different distances
- * All strips bonded and connected to a CIVIDEC [7] spectroscopic amplifier
- * Data taken with a fast oscilloscope

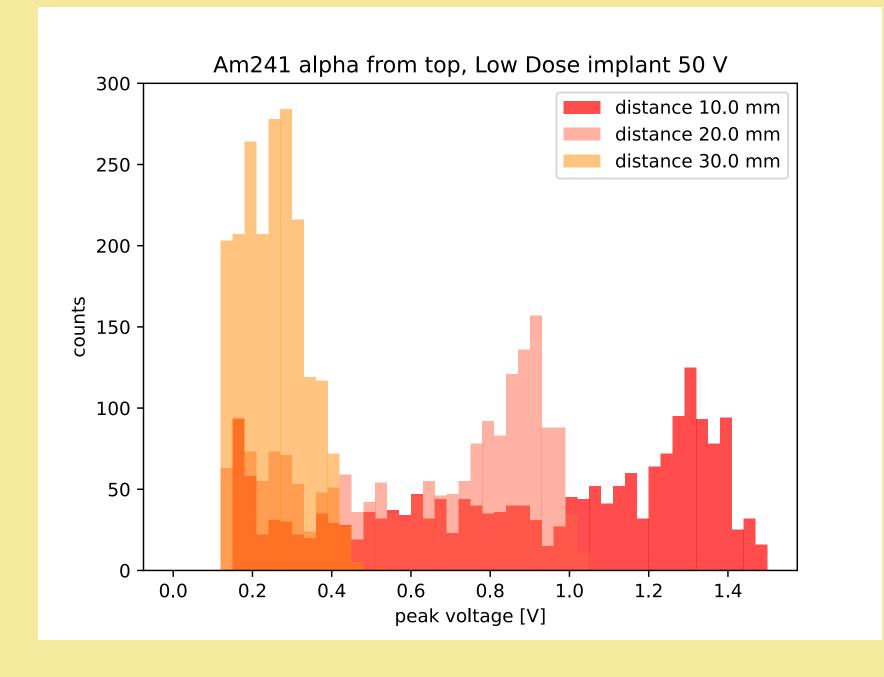




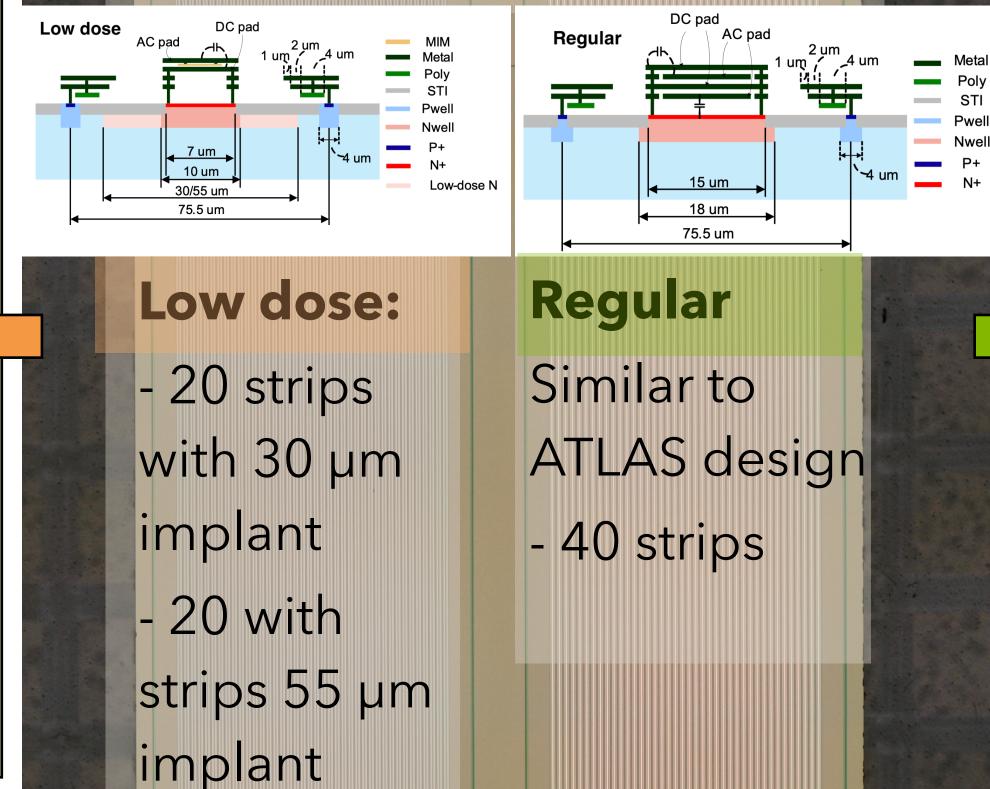
J Fachnochschule Dortmund University of Applied Sciences and Arts

Results Low Dose implant

- Alpha peak amplitude for different distances, 2000 waveforms each
- Sensor biased at 50 V (depleted)



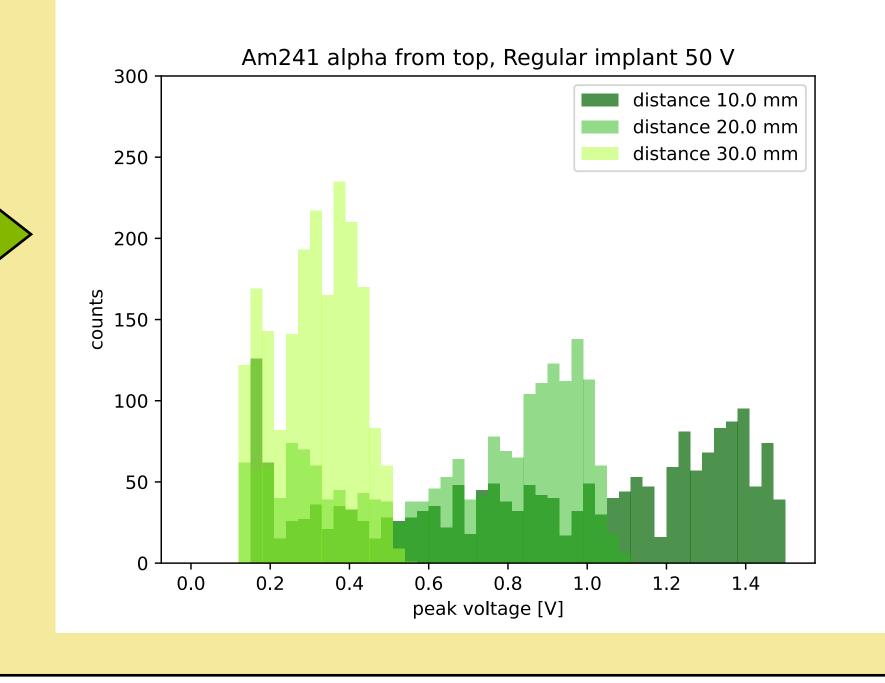
- long, with 75.5 µm pitch * Passive technology, no electronics included
- * Two strip designs:



Results Regular implant

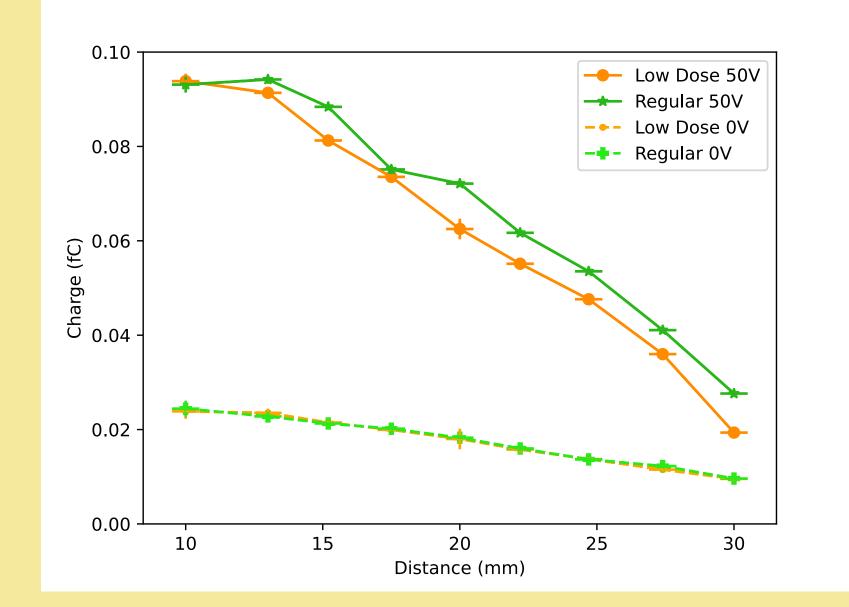
 Alpha peak amplitude for different distances, 2000 waveforms each

Sensor biased at 50 V (depleted)



Analysis

- As expected, the closer the source is from the detector more charge is deposited (less interaction with air)
- Calibration from CIVIDEC, using the literature value 12.5 mV/fC
- Data peaks fit with Landau curves



Stitching line (junction between two reticles) 1 cm² reticle Stitching line (junction between two reticles)

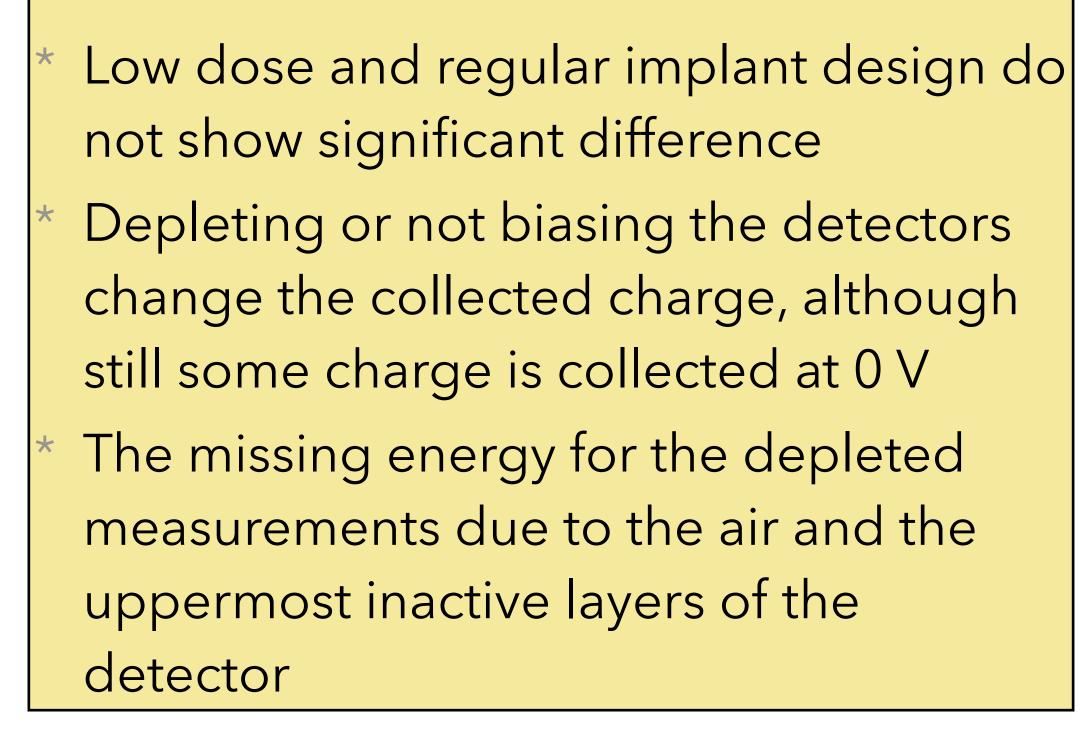
Conclusions

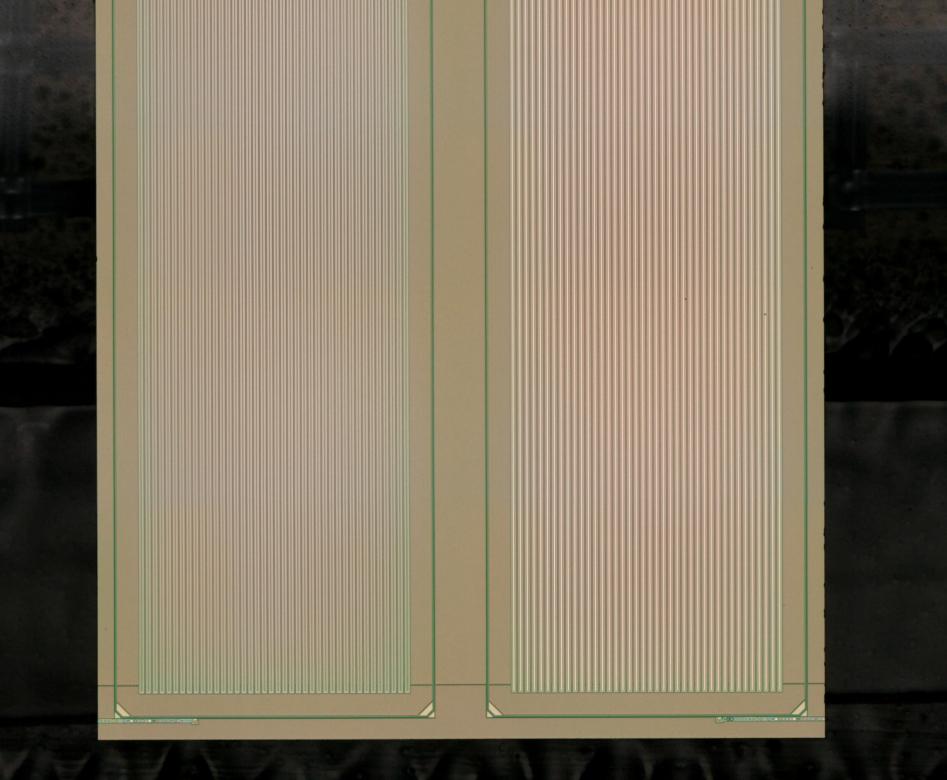
- Passive CMOS stitched strip detectors work with alpha particles
- Different energy detected at different distances for the two strip designs
- Stitching does not affect the strip performance
- Future plans:
 - Fabricate active strips
- * Full CMOS wafer strip detector

Acknowledgements

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